

Abstract

Provided is a target for use in magnetron sputtering.

This target can increase, without reducing the content of a ferromagnetic metal element in the target, the magnetic flux leakage in magnetron sputtering to a level higher than that of a conventional target.

The target is a magnetron sputtering target (10) having a ferromagnetic metal element, the magnetron sputtering target comprising: a magnetic phase (12) containing the ferromagnetic metal element; a plurality of non-magnetic phases (14,16) that each contain the ferromagnetic metal element and that are different in constituent elements or a content ratio of constituent elements; and an oxide phase(18), wherein at least one of the plurality of non-magnetic phases, namely, a non-magnetic phases (14) is more finely interdispersed with the oxide phase (18) than the magnetic phase (12).